

IN THE SPECIFICATION

Please amend the paragraph at page 1, first full paragraph as follows:

The present invention relates to a pellicle, a producing method thereof and an adhesive, and more particularly, to a pellicle used for a purpose of preventing dusts from attaching to a mask or a reticle (~~hereinafer~~ hereinafter referred simply to as mask or the like) used in the photolithography step in a process for producing an integrated circuit, to a process for producing a pellicle, and to an adhesive for pellicles.